

Title (en)
DEVICE FOR DEPOSITING THIN LAYERS ON A SUBSTRATE

Title (de)
VORRICHTUNG ZUM ABSCHIEDEN VON D NEN SCHICHTEN AUF EINEM SU BSTRAT

Title (fr)
DISPOSITIF DE DEPOT DE FINES COUCHES SUR UN SUBSTRAT

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Abstract (en)
[origin: WO03078681A1] The invention relates to a device for depositing thin layers on a substrate, comprising a process chamber (6) arranged in a reactor housing (1), the bottom of said process chamber being formed by a susceptor (7) for receiving at least one substrate and a gas inlet organ (2) being assigned to the lid of said process chamber, wherein the process gas can be introduced into the process chamber by means of a gas outlet surface which is substantially evenly distributed on the surface thereof and which points towards the susceptor. In order to prevent parasitic accumulation in the gas inlet organ, the gas outlet surface is formed by a gas-permeable diffuser plate (15), which can extend parallel to a gas outlet plate (13) having a plurality of gas outlet holes (14) arranged in the form of sieves.

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